

### **IN THE SPECIFICATION**

Please amend the specification as follows:

The pending Office Action objected to the specification as failing to provide proper antecedent basis for the term halogenated hydrocarbon. Please amend the paragraph beginning on page 10, line 2 as follows:

Another advantage of methods and devices described above includes the ability to use supercritical fluid techniques with existing cleaning processes and cleaning solutions. For example, in a current dry cleaning process, de-ionized water is used to rinse a surface of a semiconductor surface. A supercritical fluid method as described above can be used to form bubbles in the de-ionized water. Likewise, in a wet cleaning example, a solution such as H<sub>2</sub>SO<sub>4</sub> or H<sub>2</sub>O<sub>2</sub> is used to clean the semiconductor surface. A supercritical fluid method as described above can be added to this wet cleaning example to form bubbles in the H<sub>2</sub>SO<sub>4</sub> or H<sub>2</sub>O<sub>2</sub> solutions. In processes such as those used for multichip assemblies where fluxes and or organic residues are present, halogenated hydrocarbons such as chlorocarbons or chlorofluorocarbons may be used as a carrier fluid.

The broader term halogenated hydrocarbons was included in original claim 43. As such, Applicant submits that no new matter is added.